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Self-organized formation of nano-multilayer structure in the carbon-copper thin film during reactive magnetron sputtering deposition process

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1	Self-organized Formation of Nano-multilayer
2	Structure in the Carbon-Copper Thin Film during
3	Reactive Magnetron Sputtering Deposition Process
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8	ABSTRACT: Fabrication of Nano-multilayered structure film is often complex owing to its
9	fabricated process which needs to regulate a certain deposition parameter periodically. Here, we
10	demonstrated a self-organized nano-multilayered structure in carbon-copper thin films only
11	using one single sputtering target of copper in a conventional DC reactive sputtering deposition
12	process. The influence of methane concentration on the microstructure, especially on the self-
13	organized nano-multilayer, of the films were investigated by X-ray photoelectron spectroscopy
14	(XPS), Raman spectroscopy, field emission scanning electron microscopy (FESEM) and high-
15	resolution transmission electron microscopy (HRTEM). The results showed that the film
16	deposited at low methane concentration was consisted of disorder copper grains with higher
17	copper content. With increasing methane concentration, the copper content in the films decreased

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